

Inventor: Weimin Li et al.  
Title: Compositions Of Matter and Barrier Layer Compositions  
Assignee: Micron Technology, Inc.

**INFORMATION DISCLOSURE STATEMENT**  
**PURSUANT TO 37 C.F.R. " 1.56, 1.97 AND 1.98**

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a continuation application of co-pending application Serial No. 09/641,826, filed August 17, 2000. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. § 1.98(d) and MPEP § 609(2).

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: February 10, 2004

By: Jennifer J. Taylor  
Jennifer J. Taylor, Ph.D.  
Reg. No. 48,711

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-2497	Priority SERIAL NO. 09/641,826		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li et al.			
					Priority FILING DATE August 17, 2000		GROUP Unknown	
U.S. PATENT DOCUMENTS								
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate		
AA	4,474,975	10/84	Clemons et al.					
AB	5,962,581	10/99	Hayase et al.					
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AK	4,805,683	2/89	Magdo et al.					
AL	5,874,367	2/99	Dobson					
AM	5,858,880	1/99	Dobson et al.					
FOREIGN PATENT DOCUMENTS								
	Document Number	Date	Country	Class	Subclass	Translation		
						Yes	No	
AN	0 942330	9/99	EPO					
AO	9-50993	02/97	Japan				X	
AP	6-244172	09/94	Japan			X		
AQ	593,727	10/47	GB					
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AR	Withmall, R. et al., "Matrix Reactions of Methylsilanes and Oxygen Atoms", The Journal of Physical Chemistry, Vol. 92, No. 3, 1998, pp. 594-602.						
	AS	Weidman, T. et al., "New Photodefinable Glass Etch Masks for Entirely Dry Photolithography: Plasma Deposited Organosilicon Hydride Polymers", Appl. Phys. Lett., Vol. 62, No. 4, Jan. 25, 1993, pp. 372-374.						
	AT	Weidman, T. et al., "All Dry Lithography: Applications of Plasma Polymerized Methylsilane as a Single Layer Resist and Silicon Dioxide Precursor", J. Photopolym. Sci. Technol., Vol. 8, No. 4, 1995, pp. 679-686.						
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	AB	5,270,267	12/93	Ouellet					
	AC	5,541,445	7/96	Quellet					
	AD	6,022,404	02/00	Ettlinger et al.					
	AE	5,709,741	01/98	Akamatsu et al.					
	AF	4,648,904	03/87	DePasquale et al.					
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	AL	5,061,509	10/91	Naito et al.					
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	AT	Matsuura, M. et al., "A Highly Reliable Self-Planarizing Low-k Intermetal Dielectric for Sub-quarter Micron Interconnects, IEEE IEDM Tech. Dig., 1997, pp. 785-788.							
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						Yes	No		
	AM	0 588087 A2/3	03/94	EPO					
		9 055351	02/97	JP					
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	AQ	Kiermasz, A. et al., "Planarisation for Sub-Micron Devices Utilising a New Chemistry", DUMIC Conf., California, Feb. 1995, pp. 1-2.							
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	AJ	5,883,014	3/99	Chen				
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	AP	TEXT: Ralls, K. et al., "Introduction to Materials Science and Engineering", 1976 John Wiley & Sons, Inc., pp. 312-313.						
	AO	ABSTRACT: Loboda, M. et al., "Using Trimethylsilane to Improve Safety, Throughput and Versatility in PECVD Processes", Electrochemical Society Meeting Abstract No. 358, 191 <sup>st</sup> Meeting, Montreal, Quebec, Vol. MA 97-1, 1997, page 454.						
	AR	Laxman, R. et al., "Synthesizing Low-K CVD Materials for Fab Use", Semiconductor Internatl., Nov. 2000, pp. 95-102 (printed from www.semiconductor-intl.com).						
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	AA	6,017,779	1/00	Miyasaka				
	AB	6,156,674	12/00	Li et al.				
	AC	6,140,151	10/00	Akram				
	AD	5,314,724	5/94	Tsukune et al.				
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	AL	200068261A	03-2000	Japan				
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	AN		Grant, J., "Hack's Chemical Dictionary", McGraw-Hill, Inc. 1969, Fourth Edition, page 27.					
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	AQ		Shibata, N., "Plasma-Chemical Vapor-Deposited Silicon Oxide/Silicon Oxynitride Double-Layer Antireflective Coating for Solar Cells", Jap. Jour. of App. Physics, Vol. 30, No. 5, May 1991, pp. 997-1001.					
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	AK	6,133,096	10/00	Su et al.				
	AL	6,136,636	10/00	Wu				
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	AM	368687A	09-1999	TW				
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	AN		Bencher, C. et al., "Dielectric Antireflective Coatings for DUV Lithography", Solid State Technology (March 1997), pp. 109-114.					
	AO		Dammel, R.R. et al., "Dependence of Optical Constants of AZ* BARLi™ Bottom Coating on Back Conditions, SPIE Vol. 3049 (1997), pp. 963-973.					
	AP		TEXT: Heavens, O.S., "Optical Properties of Thin Solid Films", pp. 48-49.					
	AQ		TEXT: Jenkins, F. et al., "Fundamentals of Optics", Properties of Light, pp. 9-10.					
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	AA	5,933,721	8/99	Hause et al.				
	AB	5,981,368	11/99	Gardner et al.				
	AC	6,159,804	12/00	Gardner et al.				
	AD	6,130,168	10/00	Chu et al.				
	AE	6,235,591 B1	5/01	Balasubramanian et al.				
	AF	6,198,144 B1	3/01	Pan et al.				
	AG	5,801,399	9/98	Hattori et al.				
	AH	5,994,730	11/99	Shrivastava et al.				
	AI	6,040,619	3/00	Wang et al.				
	AJ	6,060,765	5/00	Maeda				
	AK	6,060,766	5/00	Mehta et al.				
	AL	6,451,504	09/02	Rolfson et al.				
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	AM	429473A	04-2001	TW				
	AN	420844A	02-2001	TW				
	AO	8046186	02-1996	Japan			X	
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AA	6,133,613	10/00	Yao et al.				
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AT	6232113	08-1994	Japan				
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		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AS							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AT							
EXAMINER					DATE CONSIDERED			
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>								

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-2497	Priority SERIAL NO. 09/641,826	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li et al.		
					Priority FILING DATE August 17, 2000		GROUP Unknown
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*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	09/234,233	01-1999	Li et al.			
	AB	6,274,292	08-2001	Holscher et al.			
	AC						
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	AI						
	AJ						
	AK						
	AL						
FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	AM						
	AN						
	AO						
	AP						
	AQ						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
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